



12. (Amended) The substrate cleaning system according to Claim 10 [or 11], wherein the chamber body 80 comprises a chemical supply section 91 for supplying cleaning solution onto a substrate surface supported by the substrate rotating unit 81, an inert gas supply section 92 for supplying inert gas so as to discharge and exchange cleaning solution, and a drain section provided in each processing bath so as to drain cleaning solution or inert gas in each processing bath.



Creation date: 11-19-2003  
Indexing Officer: ACHICU - ANDREI CHICU  
Team: OIPEBackFileIndexing  
Dossier: 09871250

Legal Date: 03-03-2003

No.	Doccode	Number of pages
1	SRNT	2

Total number of pages: 2

Remarks:

Order of re-scan issued on .....